



Correction to: Thickness dependence of properties Ga-doped ZnO thin films deposited by magnetron sputtering

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Correction to:

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In the original version of this article reference [1] was unfortunately missed and should have been included as proper citation of related work. In addition, the authors would like to make the following comments to avoid the appearance of duplicate work in these two papers.

The work reported in the original article, is on the study of variation of the thickness of thin layers on the structural and optical properties (using nanoparticles treated under air at 500 °C).

The work reported in [1] is on the effect of depositional time variations on the structural, electrical and optical properties of thin films developed by magnetron sputtering (using untreated target).

In addition, in the original publication, line 5 (part 2 Experimental details) the name of the gallium precursor is

incorrect. Therefore, the authors would like to make the following changes:

1. On page 5022, Part 2 Experimental details (line 5) the name of the gallium precursor used must be revised. The revised is given below.

After 30 min under magnetic stirring at room temperature, an adequate quantity of gallium nitrate monohydrate ($\text{Ga}(\text{NO}_3)_3 \cdot 9\text{H}_2\text{O}$) corresponding to [Ga/Zn] ratios of 0.00 and 0.03 was added.

2. The nanoparticles (ZnO:Ga) synthesized were treated under air at 500 °C in a muffle furnace for 2 h, after which we used them for the deposition of thin layers. Part 2: Line 9 (page 5022), should have. Furthermore, the samples were annealed at 500 °C in air for 2 h.

Reference

[1] “Influence of thickness on the structural, optical and electrical properties of Ga-doped ZnO thin films deposited by sputtering magnetron”; *Journal of Alloys and Compounds* 695 (2017) 697–703

The original article can be found online at <https://doi.org/10.1007/s10854-016-6158-x>.

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